

AMENDMENT UNDER 37 C.F.R. § 1.111  
U.S. APPLICATION NO.: 09/855,652

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first and second insulating films formed on a surface of a semiconductor substrate,  
a solid-state image pickup region having, as a charge transfer electrode, an electrically  
conductive material film formed on said first insulating film, and  
a peripheral circuit region formed on said semiconductor substrate other than in said  
solid-state image pickup region, a device in said peripheral circuit region being isolated from  
another device by means of an isolating electrode on said second insulating film, and said  
isolating electrode being formed of said conductive material film.

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8. (Amended) The solid-state image pickup device according to claim 6, wherein said  
third insulating film is thinner than said second insulating film, and said third insulating film has  
the same thickness as said first insulating film.

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15. (Amended) The solid-state image pickup device according to claim 11, wherein  
said second diffusion layer is formed to be separated into at least two regions on the  
semiconductor substrate below said isolating electrode, and  
at least one of the at least two regions is connected to said isolating electrode.

16. (Amended) The solid-state image pickup device according to claim 12, wherein

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said second diffusion layer is formed to be separated into at least two regions on the semiconductor substrate below said isolating electrode, and

at least one of the at least two regions is connected to said isolating electrode.

17. (Amended) The solid-state image pickup device according to claim 13, wherein said second diffusion layer is formed to be separated into at least two regions on the semiconductor substrate below said isolating electrode, and

at least one of the at least two regions is connected to said isolating electrode.

18. (Amended) The solid-state image pickup device according to claim 14, wherein said second diffusion layer is formed to be separated into at least two regions on the semiconductor substrate below said isolating electrode, and

at least one of the at least two regions is connected to said isolating electrode.

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21. (Amended) The solid-state image pickup device according to claim 1, wherein said electrically conductive material film is formed of a layered film of a polysilicon film and a metal silicide film formed on the polysilicon film.

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22. (Amended) The solid-state image pickup device according to claim 6, wherein  
said electrically conductive material film is formed of a layered film of a polysilicon film  
and a metal silicide film formed on the polysilicon film.

23. (Amended) The solid-state image pickup device according to claim 5, wherein  
said electrically conductive material film is formed of a metal film.

24. (Amended) The solid-state image pickup device according to claim 6, wherein  
said electrically conductive material film is formed of a metal film.

25. (Amended) The solid-state image pickup device according to claim 1, wherein  
a fourth insulating film is buried between electrodes formed of said electrically  
conductive material film, and

a surface of the semiconductor substrate comprising said electrodes and said fourth  
insulating film is made generally flat.

26. (Amended) The solid-state image pickup device according to claim 6, wherein

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a fourth insulating film is buried between electrodes formed of said electrically  
conductive material film, and

a surface of the semiconductor substrate comprising said electrodes and said fourth  
insulating film is made generally flat.

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38. (Amended) The method for fabricating a solid-state image pickup device according  
to claim 29, wherein

the step of patterning said electrically conductive electrode material film is followed by a  
step of burying a fourth insulating film between electrodes formed of said electrically conductive  
electrode material film including said charge transfer electrode and said isolating electrode.

39. (Amended) The method for fabricating a solid-state image pickup device according  
to claim 35, wherein

the step of patterning said electrically conductive electrode material film is followed by a  
step of burying a fourth insulating film. between electrodes formed of said electrically  
conductive electrode material film including said charge transfer electrode and said isolating  
electrode.

40. (Amended) The method for fabricating a solid-state image pickup device according  
to claim 36, wherein

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the step of patterning said electrically conductive electrode material film is followed by a step of burying a fourth insulating film between electrodes formed of said electrically conductive electrode material film including said charge transfer electrode and said isolating electrode.

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